



**Microlithography NA TC Chapter  
SEMICON West**

Marriott Marquis, California

Tuesday, July 11, 2017

10:00 to 12:00 PM PST

**Agenda**

**1.0 Call to Order**

- 1.1 Introduction
- 1.2 Required Meeting Elements
  - Standards Membership Requirement
  - Antitrust Reminder
  - Intellectual Property Reminder
  - International Meeting Guidelines
- 1.3 Agenda Review

**2.0 Review & Approval of Previous Meeting Minutes: @ NA Fall, Nov 8, 2016 Meetings**

**3.0 SEMI Staff**

- 3.1 SEMI Staff Report

**4.0 Ballot Review**

**5. Task Force Reports**

- 5.1 OASIS WG
- 5.2 Extreme Ultraviolet (EUV) Fiducial Mark Task Force
- 5.3 Extreme Ultraviolet (EUV) Mask Task Force

**6.0 Leadership and Task Force Changes**

**7.0 Old Business**

- 7.1 Standards due for Five-Year Review
  - SEMI P29-1111, Specification for Characteristics Specific to Attenuated Phase Shift Masks and Masks Blanks
  - SEMI P46-1111, Specification for Critical Dimension (CD) Measurement Information Data on Photomask by XML
- 7.2 SNARFs approaching 3-year Document Development Period
- 7.3 Previous Action Items

**8.0 New Business**

- 8.1 New TFOF and SNARF
- 8.2 Ballot Submission Authorizations
- 8.3 Action Items

**9.0 Next Meeting and Adjournment**